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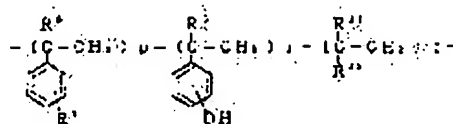
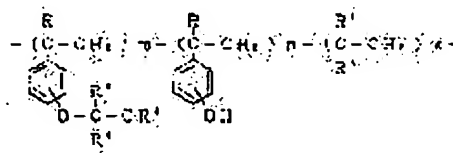
JP

(54) POLYMER COMPOSITION AND RESIST MATERIAL CONTAINING SAME

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a resist material having high transparency and high sensitivity to UV, high heat resistance, satisfactory adhesion to a substrate and high resolving power by incorporating two kinds of polymers each contg. specified monomeric units as a constituent.

SOLUTION: This polymer compsn. contains a polymer represented by formula I and contg. monomeric units each having a functional group (A) easily convertible into an alkali-soluble group by a chemical change by heating in the presence of an acid as a constituent and a



polymer represented by formula II and contg. monomeric units each having a functional group (B) having the same property as the group A but less liable to a chemical change than the group A as a constituent. In the formula I, R is H or lower alkyl, R1 is H or lower alkyl, each of R2 and R3 is H, etc., R4 is optionally halogen substd. alkyl or aralkyl and R5 is cyano, etc. In the formula II, R6 is H or lower alkyl, R7 is H, etc., R21 is H, etc., and R22 is cyano, etc.

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